

	Hits	Search Text	DBs
3	2	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error))) and ((micro\$5structure or micro\$5array) same (expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	2	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error))) and ((micro\$5structure or micro\$5array) same (expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	465	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	417	((reduc\$6 or decreas\$6 or eliminat\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	20	((reduc\$6 or decreas\$6 or eliminat\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or irradiat\$4) same (stepper or step\$7scan\$4)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	76	((reduc\$6 or decreas\$6 or eliminat\$4 or remov\$5) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask) and stepper	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	14	((reduc\$6 or decreas\$6 or eliminat\$4 or remov\$8) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist)) and ((expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or ((writ\$4 or pass\$3) near6 (multi\$5 or pluralit\$5)))) and ((mask or reticle or photomask) same (contour or (meander\$8 near5 (edge or side)))) and stepper	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	32	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and ((mask or reticle or photomask) same ((meander\$6 near14 (side or edge)) or contour or (irregular near15 edge)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	6	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4 or eliminat\$4 or remov\$5) same ((seam near5 line) or seam or (stitch\$5 near8 error) or (pattern near9 imag\$4 near5 error))) and ((expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and ((mask or reticle or photomask) same ((meander\$5 or non\$5uniform\$5 or non\$5planar or rough\$4 or irregular or strut or lattice or grill\$4) near5 (side or edge))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	57	((reduc\$6 or decreas\$6 or vary\$6 or chang\$4 or eliminat\$4 or remov\$5) same ((seam near5 line) or seam or (stitch\$5 near8 error) or (pattern near9 imag\$4 near5 error))) and ((expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and ((mask or reticle or photomask) same (meander\$5 or non\$5uniform\$5 or non\$5planar or rough\$4 or irregular or strut or lattice or grill\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	51	((reduc\$6 or decreas\$6 or eliminat\$4 or remov\$5) same ((seam near5 line) or seam or (stitch\$5 near8 error) or (pattern near9 imag\$4 near5 error))) and ((expos\$4 or illuminant\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and ((mask or reticle or photomask) same (meander\$5 or non\$5uniform\$5 or non\$5planar or rough\$4 or irregular or strut or lattice or grill\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	36	((expos\$4 or illuminat\$4 or irradiat\$4 or (light near9 source)) same defocus\$7) and ((mask or reticle or photomask) same binary same (variable or vary\$4 or chang\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	40	((microstructure or pattern\$4) same (photosensitive or photoresist) same electroplat\$4 same master same mold\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	66	430/5.ccls. and ((reduc\$6 or decreas\$6 or vary\$6 or chang\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	14	430/322.ccls. and ((reduc\$6 or decreas\$6 or eliminat\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	11	430/394.ccls. and ((reduc\$6 or decreas\$6 or eliminat\$4) same ((seam near5 line) or seam or (stitch\$5 near5 error) or (exposure near5 error) or (pattern near9 imag\$4 near5 error)) same (expos\$4 or illuminat\$4 or photolithographic\$3 or irradiat\$4 or photoresist or stepper)) and ((expos\$4 or illuminat\$4 or irradiat\$4) same (sweep or passes or (pass near5 offset) or (writ\$4 near6 (multi\$5 or pluralit\$5)))) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB